

ABSTRACT

It is an object to provide a manufacturing method of a polishing pad made from a polyurethane resin foam having very uniform, fine cells therein and a polishing pad obtained by means of the manufacturing method. It is an object to provide a polishing pad more excellent in polishing characteristics (especially, a planarization characterization) than a conventional polishing pad and having no halogen therein, and a manufacturing method thereof. It is an object to provide a polishing pad improved on dressability while a planarization characteristic and a polishing speed of a conventional polishing pad is maintained.